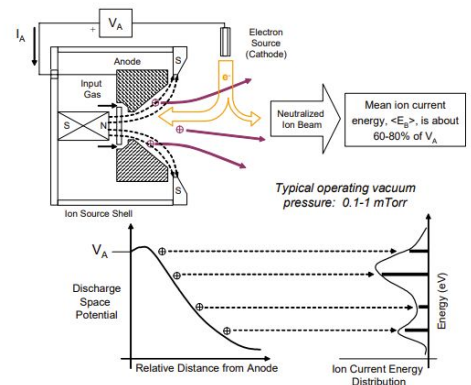
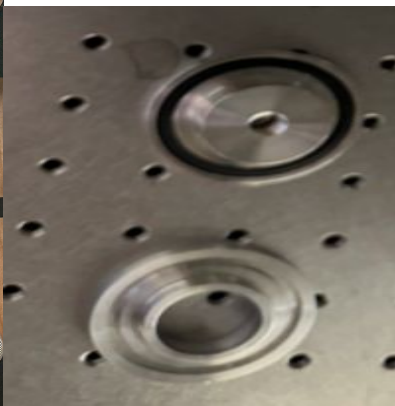


Mounting:



- A first mock of the ion source mount is completed (see left). It currently is too tall and may interfere with samples, especially with a full sized mirror, edits may be done to the mounting hole location in order to lower the height. As a reminder the source serves to help the uniformity of coating; using the low-energy ion beam to remove contaminants such as water vapor from the substrate as well as Ion assisted deposition in which a continuous flow of ions strikes the surface of the substrate to assist in film growth, adhesion, and hardness while reducing absorbed residual gas.

- We placed an order for o-rings as the ones used for the cylindrical openings in the evaporator chamber seem crushed, these have arrived and will be installed by me throughout this week. While they are adequate for now, under better vacuum, these o-rings will be highly detrimental. We are additionally doing a week long pump down to test the de-gas function of our ionization gauge.



Mirror Mount:

- The mounting holes and thick bottom pieces are planned to be used as the primary mounting mode in the chamber, we aim to have something machined that is adaptable for multiple different mirror sizes and dimensions but primarily to the pF-RICH mirror dimensions.
- The available mounting area is limited by the evaporation envelope, tall objects such as the QCM and ion source as well as the adequate distance from the evaporation source for uniform deposition.

